

ABSTRACT OF THE DISCLOSURE

A method is for manufacturing a nanostructure in-situ, at least one predetermined point on a supporting carrier. The method includes choosing a suitable material for a substrate in the carrier, creating the substrate, and preparing a template on the substrate so that the template covers the predetermined point. The template is given a proper shape according to the desired final shape of the nanostructure, and a film of nanosource material with desired dimensions is formed on the template. The film of nanosource material is made to restructure from a part of the template, thus forming the desired nanostructure. Suitably, the template includes a first and a second area which have different properties with respect to the nanosource material.